

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHEN et al.

Atty. Ref.: 2476-37; Confirmation No. 2846

Appl. No. 10/730,381

TC/A.U. 2815

Filed: 09 December 2003

Examiner: Jackson Jr., Jerome

For: PROGRAMMABLE PHOTOLITHOGRAPHIC MASK BASED ON
SEMICONDUCTOR NANO-PARTICLE OPTICAL MODULATORS

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March 23, 2009
A Monday

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT

Responsive to the Official Action dated December 22, 2008 (for
which petition is hereby made for any necessary extension of time),
please amend the above-identified application as follows: